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Abstract of the Disclosure

A semiconductor manufacturing apparatus for a photolithographic process having a  
5 coating process and a developing process is described, which includes a first port, a second  
port, a coating member, and a developing member. The first port and second port have a  
constant distance from each other, where a substrate comes in and goes out. The coating  
member, which couples the first port to the second port, carries the substrate between the first  
port and the second port and carries out the coating process. The developing member, which  
10 couples the first port to the second port and is stacked on the coating member, carries the  
substrate therebetween and carries out the developing process. The apparatus can stably  
maintain an operating ratio of equipment, and be installed in a relatively small area.

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